

Symposium (Oral) | Symposium : Fundamentals and Latest Technology Trends of Atomic Layer Process (ALP)

📅 Wed. Sep 18, 2024 1:30 PM - 7:30 PM JST | Wed. Sep 18, 2024 4:30 AM - 10:30 AM UTC 🏛️ A23 (TOKI MESSE 2F)

[18p-A23-1~17] Fundamentals and Latest Technology Trends of Atomic Layer Process (ALP)

Satoshi Hamaguchi(Osaka Univ.), Takeshi Momose(Kumamoto Univ.), Yukihiro Shimogaki(Univ. of Tokyo)

4:30 PM - 5:00 PM JST | 7:30 AM - 8:00 AM UTC

[18p-A23-9] Atomic layer etching of dielectric films using HF containing plasma at low temperature

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Keywords : plasma etching、 atomic layer process
